

1 1. A method for manufacturing an electroplating article, said method
2 comprising:

3 a) applying a conformable mask to an article comprising a first substrate
4 and a patterned resist disposed on said first substrate;
5 b) contacting a second substrate to said conformable mask such that said
6 conformable mask obtains a pattern complementary to said pattern of said resist;
7 c) separating said first substrate from said conformable mask, said
8 conformable mask remaining adhered to said article; and
9 d) removing said resist,

10 said article being capable of electroplating a pattern of metal corresponding to the
11 complement of said pattern of said conformable mask onto an electrode when said article is
12 placed in contact with the electrode in the presence of an electrolyte solution and subjected to
13 an electric field.

1 2. A method for manufacturing an electrodepositing article, said method
2 comprising:

3 a) providing a porous medium having a first surface;
4 b) treating said porous medium to create one or more nonporous regions;
5 c) applying a film to said first surface of said porous medium;
6 d) patterning said film to create a patterned mask; and
7 e) removing at least a portion of said one or more nonporous regions,

8 said article being capable of electroplating a pattern of metal corresponding to the
9 complement of said pattern of said conformable mask onto an electrode when said article is
10 placed in contact with the electrode in the presence of an electrolyte solution and subjected to
11 an electric field.

Subb/08

1 3. (New) A method of making a supported mask, comprising:
2 obtaining a first support;
3 forming a surface relief pattern on the first support;
4 applying a conformable material over the surface relief pattern;
5 pressing said conformable material using a second support and allowing the
6 conformable material to solidify and to adhere said conformable material to said second
7 support;

8 once said conformable material has adhered to said second support, pulling
9 said second support with said conformable material adhered thereto, away from said first
10 support, to leave a patterned area that is based on said surface relief pattern, and to leave said
11 first support.

1 4. (New) A method as in claim 3, wherein said conformable material includes an
2 elastomer.

1 5. (New) A method as in claim 3, further comprising etching indented areas
2 which are formed by contact with said surface relief areas, said etching continuing until said
3 indented areas extend through to said second support.

1 6. (New) A method as in claim 3, wherein said second support is porous, and
2 further comprising initially blocking pores prior to said pressing of said second support, and
3 unblocking the blocked pores after said pulling.

1 7. A method of making a supported mask, comprising:
2 obtaining a support;
3 applying at least one layer of dielectric material to said support; and
4 exposing said layer to patterned light to substantially remove said layer from
5 said support in exposed areas.

Subb/09